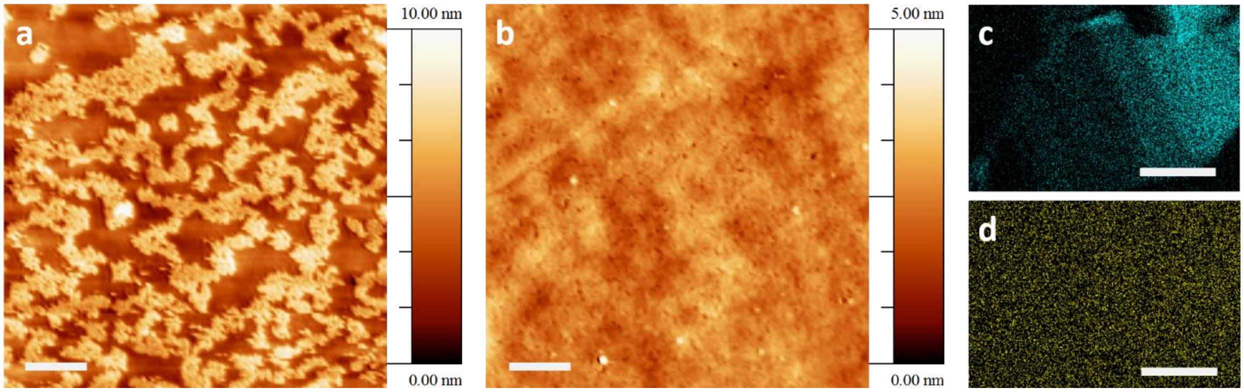

Figure 1. AFM scans after 3 nm of Al_2O_3 deposited on (a) untreated MoS_2 and (b) MoS_2 immersed in $HAuCl_4$ solution for 10 seconds prior to deposition. EDX maps of a typical flake show (c) sulfur and (d) aluminum distribution. The scale bar is 500 nm for (a) and (b) and 10 µm for (c) and (d).